

Day : Tuesday
Date: 8/10/2004
Time: 14:55:18



PALM INTRANET

Inventor Information for 10/693842

Inventor Name	City	State/Country
NOMURA, MAMIKO	KANUMA-SHI	JAPAN
HASEGAWA, MASATOSHI	CHIBA-SHI	JAPAN
ISHII, JUNICHI	KANUMA-SHI	JAPAN
AKAMATSU, TADASHI	KANUMA-SHI	JAPAN

[Appln Info](#) [Contents](#) [Petition Info](#) [Atty/Agent Info](#) [Continuity Data](#) [Foreign Data](#)

Search Another: Application# or Patent#
PCT / / or PG PUBS #
Attorney Docket #
Bar Code #

To go back use Back button on your browser toolbar.

Back to [PALM](#) | [ASSIGNMENT](#) | [OASIS](#) | [Home page](#)

L Number	Hits	Search Text	DB	Time stamp
1	1906041	photosensitive resin composition and polyimide and (photosensitizer or initiator)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/08/10 16:18
2	382974	(photosensitive resin composition and polyimide and (photosensitizer or initiator)) and o quinone diazide	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/08/10 16:19
3	376746	((photosensitive resin composition and polyimide and (photosensitizer or initiator)) and o quinone diazide) and (?trihydroxybenzophenone o naphthoquinone diazide sulfonic ester)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/08/10 16:20
4	29796	((((photosensitive resin composition and polyimide and (photosensitizer or initiator)) and o quinone diazide) and (?trihydroxybenzophenone o naphthoquinone diazide sulfonic ester)) and cyclohexane	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/08/10 16:21
5	0	((((photosensitive resin composition and polyimide and (photosensitizer or initiator)) and o quinone diazide) and (?trihydroxybenzophenone o naphthoquinone diazide sulfonic ester)) and cyclohexane) and ?diaminocyclohexane	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/08/10 16:21
6	0	((((photosensitive resin composition and polyimide and (photosensitizer or initiator)) and o quinone diazide) and (?trihydroxybenzophenone o naphthoquinone diazide sulfonic ester)) and cyclohexane) and ?methylenebiscyclohexane	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/08/10 16:31
8	26	((((photosensitive resin composition and polyimide and (photosensitizer or initiator)) and o quinone diazide) and (?trihydroxybenzophenone o naphthoquinone diazide sulfonic ester)) and cyclohexane) and 522/164.ccls.) and (polyamic acid or polyimide precursor or polyamide acid)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/08/10 16:22
9	22	((((((photosensitive resin composition and polyimide and (photosensitizer or initiator)) and o quinone diazide) and (?trihydroxybenzophenone o naphthoquinone diazide sulfonic ester)) and cyclohexane) and 522/164.ccls.) and (polyamic acid or polyimide precursor or polyamide acid)) and (film or layer)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/08/10 16:23
11	556604	(((((((photosensitive resin composition and polyimide and (photosensitizer or initiator)) and o quinone diazide) and (?trihydroxybenzophenone o naphthoquinone diazide sulfonic ester)) and cyclohexane) and 522/164.ccls.) and (polyamic acid or polyimide precursor or polyamide acid)) and (film or layer)) and alicyclic) and sulfonic ester	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/08/10 16:23
10	11	(((((((photosensitive resin composition and polyimide and (photosensitizer or initiator)) and o quinone diazide) and (?trihydroxybenzophenone o naphthoquinone diazide sulfonic ester)) and cyclohexane) and 522/164.ccls.) and (polyamic acid or polyimide precursor or polyamide acid)) and (film or layer)) and alicyclic	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/08/10 16:23
7	26	(((photosensitive resin composition and polyimide and (photosensitizer or initiator)) and o quinone diazide) and (?trihydroxybenzophenone o naphthoquinone diazide sulfonic ester)) and cyclohexane) and 522/164.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/08/10 16:30
12	1730	(((photosensitive resin composition and polyimide and (photosensitizer or initiator)) and o quinone diazide) and (?trihydroxybenzophenone o naphthoquinone diazide sulfonic ester)) and cyclohexane) and (polyamic acid or polyimide precursor) and photoinitiator	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/08/10 16:31

13	2	(((((photosensitive resin composition and polyimide and (photosensitizer or initiator)) and o quinone diazide) and (?trihydroxybenzophenone o naphthoquinone diazide sulfonic ester)) and cyclohexane) and (polyamic acid or polyimide precursor) and photoinitiator) and imidiz?	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/08/10 16:34
14	3	(((((photosensitive resin composition and polyimide and (photosensitizer or initiator)) and o quinone diazide) and (?trihydroxybenzophenone o naphthoquinone diazide sulfonic ester)) and cyclohexane) and (polyamic acid or polyimide precursor) and photoinitiator) and ?cyclohexane	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/08/10 16:36
15	40	(((((photosensitive resin composition and polyimide and (photosensitizer or initiator)) and o quinone diazide) and (?trihydroxybenzophenone o naphthoquinone diazide sulfonic ester)) and cyclohexane) and (polyamic acid or polyimide precursor) and photoinitiator) and ?cyclohexane (((((photosensitive resin composition and polyimide and (photosensitizer or initiator)) and o quinone diazide) and (?trihydroxybenzophenone o naphthoquinone diazide sulfonic ester)) and cyclohexane) and (polyamic acid or polyimide precursor) and photoinitiator) and methylene	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/08/10 16:42
16	174	near3 cyclohexane (522/164).CCLS.	USPAT	2004/08/10 17:07